

a chamber body;
a substrate support member disposed within the chamber body;
a retaining ring coupled to the chamber body, wherein the retaining ring has a feedthrough hole formed therein;
a chamber lid coupled to the retaining ring, wherein the chamber lid forms a fluid inlet, a fluid outlet, and a temperature control channel, and wherein the temperature control channel is fluidly connected to the fluid inlet and fluid outlet; and
a feedthrough disposed in the feedthrough hole fluidly connected to the temperature control channel

121. (New) A processing chamber comprising:

a chamber body;
a substrate support member disposed within the chamber body;
a retaining ring coupled to the chamber body, wherein the retaining ring has a feedthrough hole formed therein;
a chamber lid coupled to the retaining ring, wherein the chamber lid forms a fluid inlet, a fluid outlet, and a temperature control channel, and wherein the temperature control channel is fluidly connected to the fluid inlet and fluid outlet; and
a feedthrough disposed in a feedthrough hole, wherein the feedthrough is fluidly connected to the temperature control channel, and wherein the feedthrough attaches the chamber lid to the retaining ring.

122. (New) A processing chamber comprising:

a chamber body;
a substrate support member disposed within the chamber body;
a retaining ring coupled to the chamber body, wherein the retaining ring has a feedthrough hole formed therein;
a chamber lid for coupling energy from an energy source into an interior portion of the chamber body, wherein the chamber lid forms a fluid inlet, a fluid outlet, and a temperature control channel, and wherein the temperature control channel is fluidly connected to the fluid inlet and fluid outlet; and